

The effect of SiO₂ addition on the development of low- Σ grain boundaries in PTC thermistors

M.A. Zubair, C. Leach*

Materials Science Centre, School of Materials, University of Manchester, Manchester, M1 7HS, UK

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Abstract

Electron backscatter pattern analysis has been used to characterise, using the coincidence site lattice model, the distribution of grain boundary structures in a series of BaTiO₃ based positive temperature coefficient of resistance (PTC) thermistors, prepared with 0, 1.0, 2.0 and 3.0 at.% SiO₂ additions. As the SiO₂ content was raised, the proportion of random, high-angle grain boundaries in the microstructure increased steadily from 85.7% to 89.6%, while the proportion of grain boundaries indexable in the range $\Sigma 3$ – $\Sigma 29$ decreased from 14.3% to 10.4%, and the $\Sigma 3$ grain boundary population fell from 5.9% to 3.6%. At the same time the proportion of $\Sigma 3$ twin boundaries remained approximately constant at $3.0 \pm 0.3\%$. Significantly more $\Sigma 3$ grain boundaries than would be expected in a randomly oriented, untextured material were observed in all samples. The variation in grain boundary types with SiO₂ addition is discussed in terms of grain boundary energy and its effect on PTC performance. © 2009 Elsevier Ltd. All rights reserved.

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1. Introduction

Positive temperature coefficient of resistance (PTC) thermistors, based on sintered, polycrystalline donor and acceptor co-doped BaTiO₃ ceramics show a significant increase in grain boundary resistivity at temperatures just above the ferro- to para-electric transition temperature, T_C . This PTC effect is attributed to the appearance of a back-to-back Schottky-type grain boundary potential barrier just above T_C , and arises from the combined effects of the disappearance of spontaneous polarisation, the temperature dependency of dielectric constant and the presence of filled acceptor traps at the grain boundaries^{1–4}.

It has been reported widely that the magnitude and temperature profile of the resistance jump associated with the PTC transition can differ significantly between individual grain boundaries^{5–9}. These variations have previously been attributed to microchemical inhomogeneities^{10,11} or to differences in interface geometry, the latter often being described in terms of the coincidence-site lattice (CSL) model¹². Using CSL terminol-

ogy it has been reported that $\Sigma 3$, $\Sigma 5$ and $\Sigma 9$ grain boundaries characteristically tend to show little or no PTC effect^{13–16}, whereas random, high-angle grain boundaries generally exhibit large resistance jumps in the PTC region. These differences in behaviour with grain boundary type have been attributed to changes in the magnitude of the oxygen diffusion coefficient, which affects the rate of grain boundary reoxidation during the cooling stage of the sintering cycle and hence the density of occupied interface states in the final microstructure¹⁵.

A previous study of a sintered BaTiO₃ found that 9.0% of all interfaces could be indexed as $\Sigma 3$, a value greatly in excess of the 2.7% calculated to occur by chance in a microstructure composed of randomly oriented grains¹⁷, while a subsequent study of a commercial PTC thermistor, with 2.0% SiO₂ addition, reported that 4.7% of all grain boundaries were found to have a $\Sigma 3$ misorientation¹⁸. In the latter study it was also noted that this population of $\Sigma 3$ grain boundaries formed at an early stage of sintering and was retained in the microstructure during grain growth. The observation that such grain boundary types, which are reported to be PTC inactive^{13,14}, can form preferentially during sintering is important in attempts to optimise the performance of PTC thermistors, since microstructures containing a significant proportion of grain boundaries where the PTC effect is weak, or absent, are undesirable.

* Corresponding author.

E-mail address: colin.leach@manchester.ac.uk (C. Leach).

SiO₂ has long been added to BaTiO₃ as a sintering and performance aid, lowering the sintering temperature by promoting liquid-phase sintering, reducing the grain size distribution and allowing the formation of semiconducting grains at lower temperatures¹⁹. It has also been reported that the addition of SiO₂ decreases the resistivity of the thermistor below T_C , and reduces the magnitude of the resistivity jump, while displacing the temperature of peak resistivity to higher temperatures, which also has the effect of reducing the gradient of the characteristic PTC resistance-temperature curve in the PTC region²⁰.

In this contribution electron backscatter pattern (EBSP) analysis has been used to investigate the role of SiO₂ addition on microstructural development in PTC thermistors, particularly with regard to grain boundary structure and morphology.

2. Method

Four thermistor samples, containing 0, 1.0, 2.0 and 3.0 at.% SiO₂ additions, were prepared by a mixed oxide route from (Ba,Ca)TiO₃, co-doped with a rare earth donor and 0.1% Mn acceptor ions. Powder compacts were pressed and sintered in air at a temperature of 1300 °C for 1 h and cooled at 5 °C min⁻¹, producing fully sintered, dense pellets 8 mm in diameter and 2 mm in thickness. Cross-sections of the pellets were prepared for microstructural analysis by grinding, diamond polishing, and finishing with a colloidal silica solution to produce a near strain-free surface finish.

Microstructural characterisation was carried out using backscattered electron (BS) imaging and EBSP analysis, in a Phillips XL30 FEGSEM equipped with an HKL EBSP system

and software²¹. The step size during analysis was 0.2 μm, allowing several data points to be collected from within each grain. An in-house program²² was used to establish the relative abundances of low Σ interfaces, from Σ3 to Σ29 inclusive, that were present in the thermistor. All grain boundaries not indexable in this way were classified as random, high-angle. High resolution microscopy of grain boundary structures was carried out using a TECNAI F30 300 keV transmission electron microscope (TEM).

3. Results

Resistance-temperature graphs for these thermistors have been presented previously²⁰. Fig. 1(a–d) shows BS images of the PTC thermistors with SiO₂ additions of 0, 1.0, 2.0 and 3.0 at.% respectively. Twinning is observed in all samples. The major twins bisecting the grains have a Σ3 misorientation, but were considered separately from the grain boundaries for the purpose of establishing interface population statistics. The mean grain size was measured using the linear intercept technique and lay in the range 6.3 ± 0.5 μm for all samples, indicating that SiO₂ additions of up to 3.0 at.% do not have a significant effect on overall grain growth. However, increasing the SiO₂ content did reduce the grain size distribution markedly and cause the predominant grain shape to change from rounded to square, due to the development of a {100} habit. The change in grain shape suggests that in BaTiO₃ the energies of crystallographically distinct grain faces are modified by the addition of SiO₂, with the overall consequence that the relative surface energy and

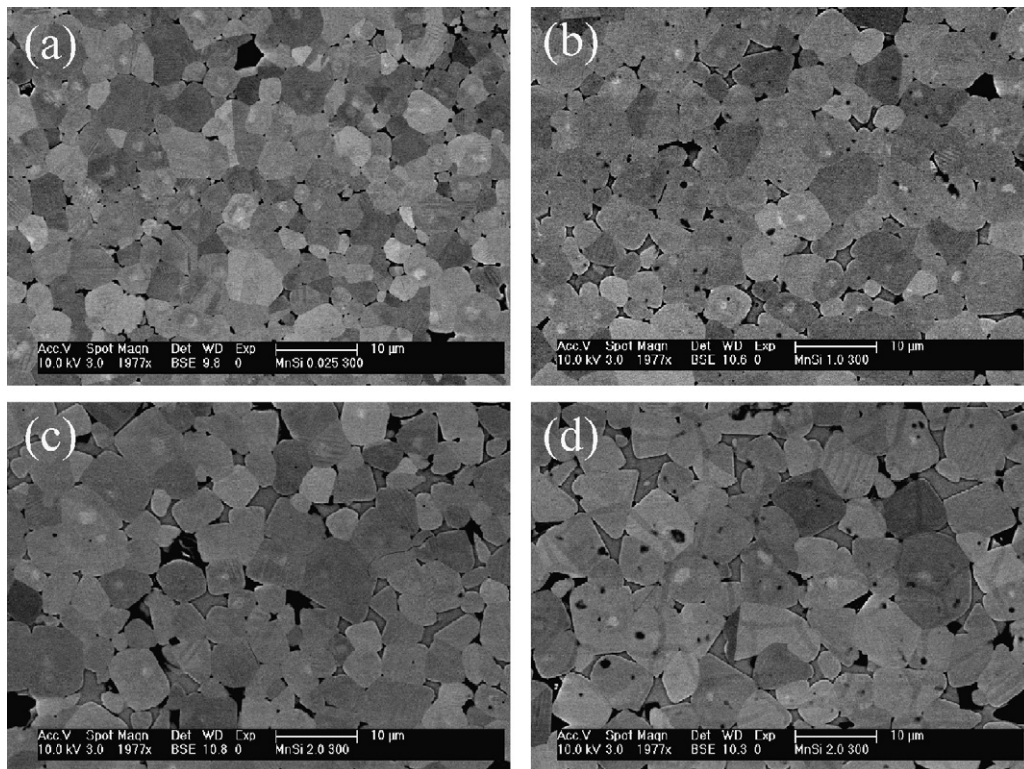


Fig. 1. Backscattered electron images of samples with (a) 0 at.% SiO₂ (b) 1.0 at.% SiO₂ (c) 2.0 at.% SiO₂ (d) 3.0 at.% SiO₂. Scale bar = 10 μm.

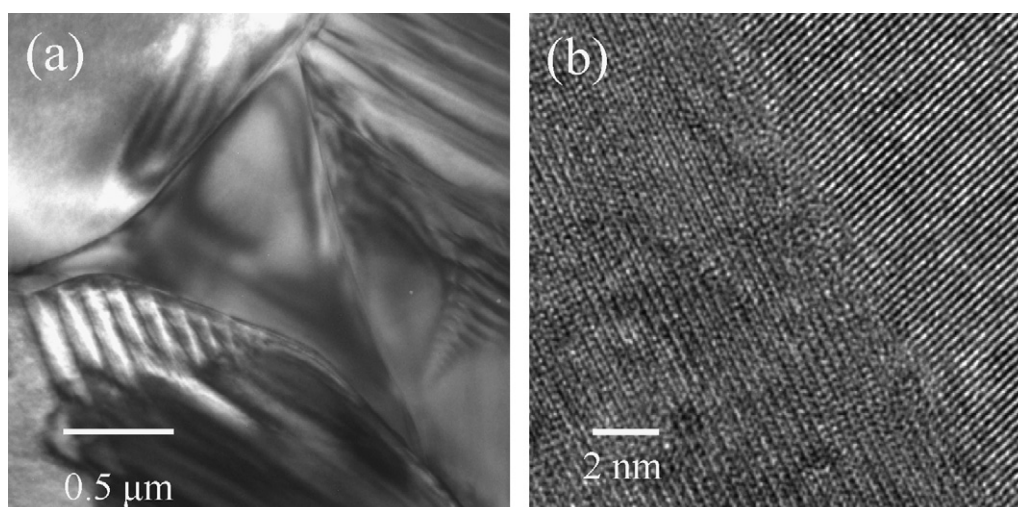


Fig. 2. TEM images of (a) triple junction containing second phase (scale bar = 0.5 μm), and (b) high resolution image of 'clean' grain boundary (scale bar = 2 nm).

growth rate of the $\{100\}$ planes is reduced as the SiO_2 content is increased, eventually causing the $\{100\}$ habit to dominate the microstructure.

XRD identified the second phase, present in all samples with SiO_2 addition, as fresnoite. Its distribution was limited to triple junctions (Fig. 2a), with no evidence, even in high resolution TEM images, for an intergranular film that would suggest grain boundary wetting (Fig. 2b). Cheng²³ also noted an absence of grain boundary film in his study of the effect of SiO_2 and TiO_2 additions in this system. In order to explain the microstructural changes he observed, it was proposed that SiO_2 or TiO_2 addition led to the formation of a wetting silicate phase at PTC thermistor grain boundaries during sintering, but that this film withdrew on cooling, and collected at triple junctions. Choi et al.²⁴ observed intergranular films of varying thickness in TiO_2 -rich BaTiO_3 and attributed their development to the progressive penetration of a liquid-phase, which initially accumulated at triple junctions, along the grain boundaries. Our observation of grain size homogenisation and changes in grain morphology with SiO_2 addition are also most simply explained in terms of a percolating, second phase film, which was present at the grain boundaries during sintering, and which became more prevalent with increasing SiO_2 addition. This film modified the surface and interfacial energies of the BaTiO_3 grains, causing them to grow with differing morphologies, possibly as a consequence of the change in surface Ba:Ti ratio as fresnoite formed, but subsequently withdrew to triple junctions on cooling, to give the final distribution in the microstructure, in line with our observations and the proposals of other workers^{23,24}.

The distribution of grain boundary types and twin structures present in each sample were characterised using EBSD analysis. An area close to the centre of each pellet, approximately $250\ \mu\text{m} \times 200\ \mu\text{m}$ in size, was selected for analysis, allowing around 3000 interfaces to be characterised in each case (Table 1). The interfaces were classified, where possible, using CSL nomenclature for Σ values up to $\Sigma 29$: any remaining boundaries that could not be indexed in this way were classified as random, high-angle. Fig. 3(a–d) are $\langle 100 \rangle$ pole figures showing the distribution of grain orientations in each sample. The uniformity of the distributions indicates that there is no significant preferred grain orientation and hence no crystallographic texture that might influence the distribution of grain boundary types found within the thermistors. Table 1 summarises the grain boundary misorientation data by listing the proportions of high-angle grain boundaries and low- Σ grain boundaries in each sample as a function of the total grain boundary population. The abundances of $\Sigma 3$ twin boundaries within each microstructure, as a function of the total interface population, are also included. Several trends are apparent. On increasing the SiO_2 content from 0% to 3.0 at.% the proportion of random high-angle grain boundaries increases progressively from 85.7% to 89.6%, reducing the population of grain boundaries indexable in the range $\Sigma 3$ – $\Sigma 29$ from 14.3% to 10.4%. Within this group the $\Sigma 3$ grain boundary population shows the most significant change, decreasing from 5.9% to 3.6%. Given the sample size, both of these variations are statistically significant and systematic with SiO_2 addition. The distribution and variation with SiO_2 addition of all Σ indexable grain boundaries are summarised in

Table 1
Grain boundary and twin population statistics as a function of SiO_2 addition.

SiO_2 content (at.%)	Total grain boundaries analysed	% high-angle grain boundaries	% $\Sigma 3$ – $\Sigma 29$ grain boundaries	% $\Sigma 3$ grain boundaries	% $\Sigma 5$ – $\Sigma 29$ grain boundaries	% $\Sigma 3$ twin boundaries
0.0	2867	85.7	14.3	5.9	8.4	2.8
1.0	3691	86.0	14.0	5.1	8.9	2.7
2.0	3447	87.6	12.4	4.3	8.1	3.3
3.0	3635	89.6	10.4	3.6	6.8	3.3

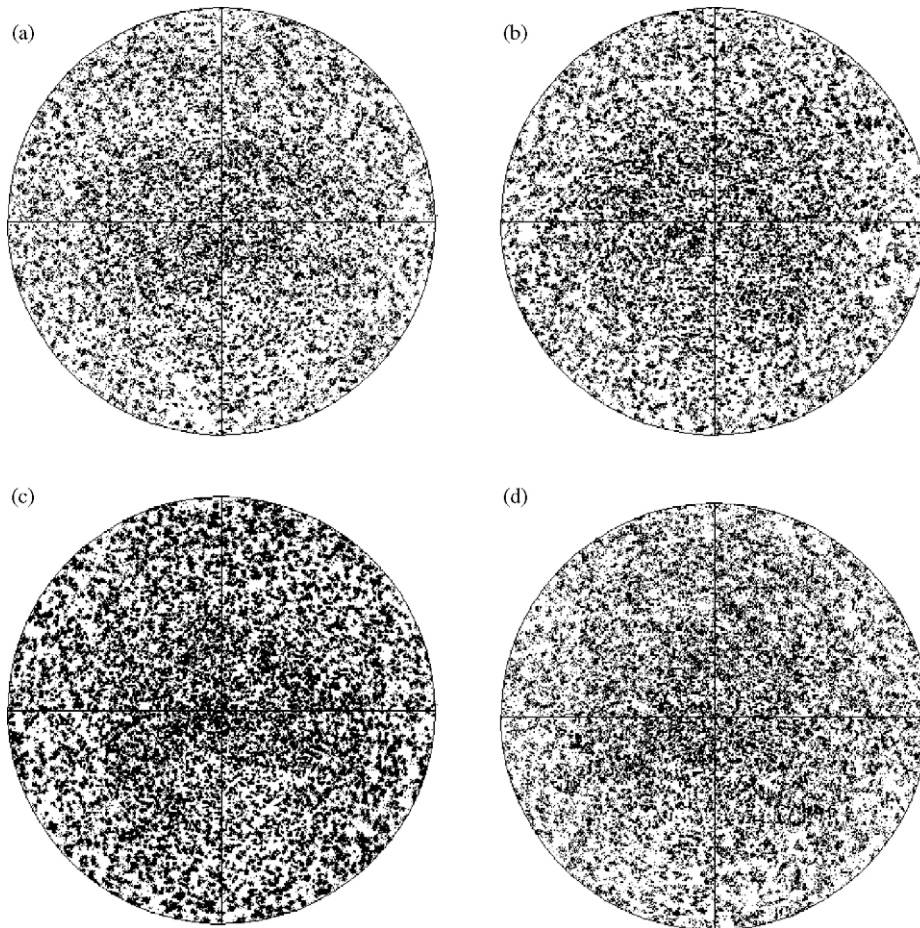


Fig. 3. {100} polefigures showing grain orientation distributions in samples sintered with SiO₂ additions of (a) 0 at.%, (b) 1.0 at.%, (c) 2.0 at.%, and (d) 3.0 at.%.

Fig. 4, from which it can be seen that other low- Σ grain boundary structures, notably $\Sigma 5$, $\Sigma 9$ and $\Sigma 11$, also show a small reduction in abundance with increasing SiO₂ content. However in most other cases any variation is difficult to confirm due to statistical noise associated with the small numbers involved, although when grain boundaries in the range $\Sigma 5$ – $\Sigma 29$ are considered together, there is an overall decrease in the total population from 8.4% to 6.8%. Despite this progressive reduction in the proportion of low- Σ grain boundaries with SiO₂ addition, the $\Sigma 3$ twin population remained relatively constant throughout, lying in the

range $3.0 \pm 0.3\%$, which is consistent with a previous study that noted the twin density is controlled by mean grain size, and reflects a relaxation of accumulated stress¹⁸.

In all of the samples studied here there are significantly more $\Sigma 3$ grain boundaries than would be expected to occur by chance within a random distribution of grain orientations (around 2.7%); an observation that is in agreement with the findings of earlier workers^{17,18}. We also note that with SiO₂ addition there are progressive decreases, both in the proportion of $\Sigma 3$ grain boundaries, and in the total number of grain boundaries indexable in the range $\Sigma 5$ – $\Sigma 29$. The tendency to form and retain a high proportion of Σ indexable grain boundaries in the sintered microstructure is therefore strongest in the samples where there is little or no SiO₂ addition. We believe that the proportion of Σ grain boundaries decreases as the SiO₂ content is increased because the presence of SiO₂ changes the relative energies of differently structured grain boundaries during sintering with the consequence that their relative abundances in the microstructure change. Previous workers have shown using a statistical approach, that in many microstructures, certain crystal faces occur preferentially at grain boundaries with specific misorientations and hence that grain boundaries preferentially adopt certain structures in sintered materials^{25–27}. The particular structures that are favoured depend on the system: for example SrTiO₃

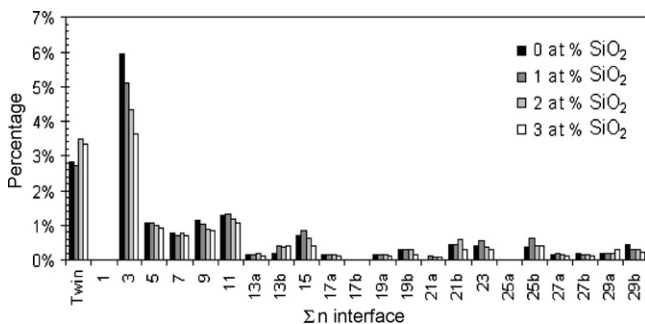


Fig. 4. Histogram showing variation of low- Σ grain boundary abundance by Σ value, as a function of SiO₂ addition.

shows a strong tendency to form $\{100\}$ type grain boundary planes at 15° grain misorientation²⁵, in MgO $[100]$ planes occur preferentially at all misorientations²⁶, and in alpha-brass asymmetric $\{110\}$ tilt boundaries and $\{111\}$ twist boundaries were found to predominate²⁷. The driving force is an overall energy reduction through the preferential formation and retention of low energy grain boundary structures, and has been validated by the derivation of an approximately inverse relationship between the energy of a particular grain boundary structure and its frequency of occurrence in the microstructure²⁸.

CSL Σ boundaries are defined using geometrical criteria¹² that indicate grain boundary misorientations where a simple interfacial atomic configuration might occur, reducing the energy of the grain boundary. In BaTiO₃ this is believed to be the case for $\Sigma 3$ grain boundaries, which occur preferentially in the microstructure, and which are commonly described as coherent, low energy structures with low defect concentrations and little or no impurity segregation²⁹. These latter characteristics are consistent with the weak PTC behaviour associated with these grain boundary types^{13,14,29} and are indicative of limited wetting and dopant transport along these grain boundaries during sintering, reducing trap formation and activation. The weak PTC effect, similarly reported for $\Sigma 5$ and $\Sigma 9$ grain boundaries¹² also suggests that these grain boundaries also adopt low energy structural configurations with a reduced driving force for dopant segregation at the interface. The energies of ‘randomly oriented’ high-angle grain boundaries, however, are generally accepted to be higher than ‘special’, low- Σ grain boundaries due to increased lattice mismatch and associated interfacial disorder³⁰. Consequently there is the possibility that the energy of a high-angle grain boundary may be lowered significantly by the incorporation of appropriate segregants that can accommodate lattice strain, or a low melting-point sintering aid that wets the interface²⁹.

As the SiO₂ content is increased, the volume of liquid phase formed at the sintering temperature will increase. If it is the case, as has previously been suggested²³, that the liquid does not remain confined to triple junctions at the peak sintering temperature, then there must either be an increase in grain boundary coverage by the film, or an overall increase in its thickness^{23,24}. A recent study of grain boundary structures in doped Al₂O₃ demonstrated that a series of interfacial phases with differing structures can form and co-exist in the same sample with their energies, and hence populations, governed by factors such as grain boundary type, additive levels, and sintering temperature³¹. Each structure was associated with a grain boundary of different mobility, a property which is also dependent on interfacial energy, demonstrating that film structure and overall grain boundary energy are closely related. In our case the interfacial energy of high-angle grain boundaries is also likely to be interlinked with the progressive, concomitant change in crystal habit towards $\{100\}$ with increasing SiO₂.

Thus in BaTiO₃ a mechanism exists to reduce progressively the overall energy difference between the high-angle and certain low- Σ grain boundaries during sintering through the incorporation of an increasing volume of a wetting phase, which contains dissolved grain boundary segregants, and which only effec-

tively percolates the higher energy, high-angle grain boundaries. This has the consequence that, with increasing SiO₂, the energy advantage associated with the formation of a high proportion of low-energy, low- Σ grain boundaries, and $\Sigma 3$ grain boundaries in particular but possibly also $\Sigma 5$, $\Sigma 9$ and $\Sigma 11$, is reduced leading to a lower population of such interfaces in the ceramic, as we observe. The progressive increase in the proportion of random, high-angle grain boundaries and the increasing development of $\{100\}$ habit with SiO₂ addition further indicates that this reduction in grain boundary energy associated with the high-angle grain boundaries, when compared with certain low- Σ grain boundaries, occurs cumulatively with increasing SiO₂.

Since $\Sigma 3$, $\Sigma 5$ and $\Sigma 9$ interfaces have all been reported as being PTC inactive, or at least to show a significantly reduced PTC effect^{14,15}, a high proportion of such grain boundaries in PTC thermistors will have a significant effect in modifying the overall device performance, especially with regard to the overall magnitude of the PTC jump and the homogeneity of current flow during high power switching transients. The combined total of $\Sigma 3$, $\Sigma 5$ and $\Sigma 9$ interfaces in our samples reduced from 8.1% to 5.4% on increasing the SiO₂ level from 0 to 3 at.%, the majority of this change coming from the reduction in the proportion of $\Sigma 3$ grain boundaries, although downward trends were also observed in the $\Sigma 5$ and $\Sigma 9$ grain boundary populations. Thus although there still remains the possibility of a significant number of poorly performing PTC thermistor grain boundaries being present in the microstructure, their overall population can be reduced by a third with 3.0 at.% SiO₂ addition.

4. Conclusions

A series of BaTiO₃ based PTC thermistors was prepared with SiO₂ additions in the range 0–3.0 at.%, and the proportions of grain boundaries corresponding to certain CSL types were characterised. The samples were untextured, but all contained significantly more $\Sigma 3$ grain boundaries than would be expected by chance. The proportion of $\Sigma 3$ grain boundaries decreased significantly with increasing SiO₂ addition, as did the overall population of other grain boundaries in the range $\Sigma 5$ – $\Sigma 29$, with $\Sigma 5$, $\Sigma 9$ and $\Sigma 11$ grain boundaries independently showing small reductions with increasing SiO₂. Simultaneously the proportion of high-angle grain boundaries increased, while the abundance of $\Sigma 3$ twin boundaries in the microstructure remained approximately constant. The change in the proportions of grain boundary structural types with SiO₂ addition was explained in terms of preferential wetting of random, high-angle grain boundaries by a SiO₂ rich film at the sintering temperature, which reduces their energy, whilst having little effect on the energies of other low-energy low- Σ boundaries.

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